

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Chih-Ming Ke  
Application No.: 10/047,266 (CONF 4511)  
Filed: 1/14/2002  
Title: Reducing photoresist shrinkage via plasma treatment  
Attorney Docket No.: 67,200-641

Group Art Unit:  
1765  
Examiner:  
Kin Chan Chen

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Date: Mar. 11, 2004

Kathy Dixon

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3/18/04 K-cc

SUPPLEMENTAL AMENDMENT

Dear Sir:

In response to an Advisory Action mailed March 5, 2004, and as a result of a telephone conference with Examiner Chen on March 11, 2004, please enter the following amendments and consider the following remarks.